

## Arsenic, As

Application : Arsenic is source materials for N-type conductive impurities for single crystal silicon growth and N-type ion implantation doping process.

### Arsenic, 6N

Metallic Impurity	Spec (ppm)	Analysis Method
Al	< 0.1	ICP-AES
Bi	< 0.5	ICP-AES
Cr	< 0.1	ICP-AES
Cu	< 0.05	ICP-AES
Fe	< 0.2	ICP-AES
Mg	< 0.1	ICP-AES
Mn	< 0.1	ICP-AES
Ni	< 0.2	ICP-AES
Pb	<0.5	ICP-AES
Si	< 0.2	ICP-AES
Zn	< 0.05	ICP-AES

\* ICP-AES : Inductively Coupled Plasma Atomic Emission Spectroscopy